

Technical datasheet

AZ LNR-003 Data Package

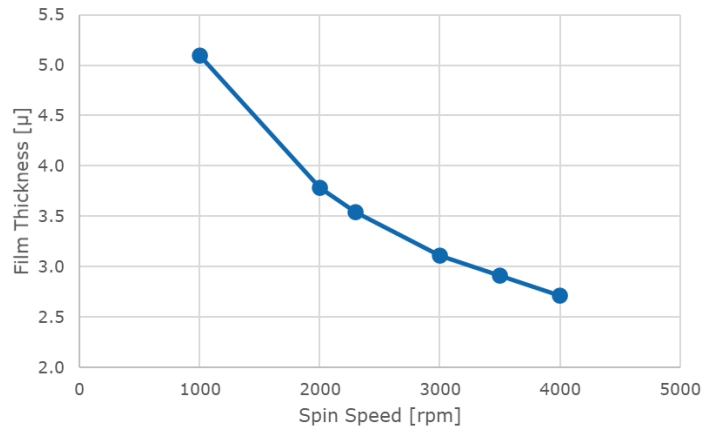
Introduction of UV negative tone resist for Lift-off

PROCESS CONDITION (ISOLATED TRENCHES: 5 μ M)

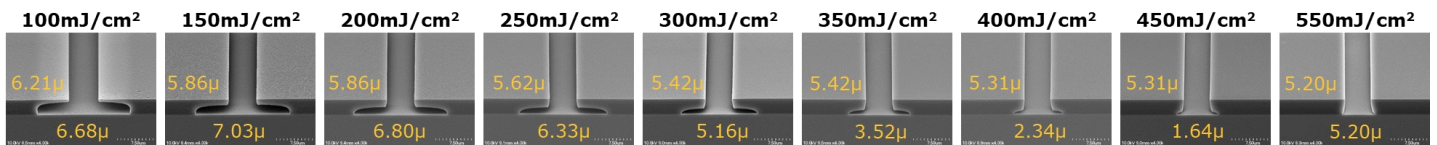
Substrate: Si-wafer
 FT: 3.5 μ m
 PAB: 120°C/120s
 PEB: 100°C/90s
 Spin Speed: 2300rpm
 Dev: 60s; AZ 300 MIF
 Exposure: ASML i-line NA 0.48 stepper

SPIN CURVE

Spin curve of AZ LNR-003

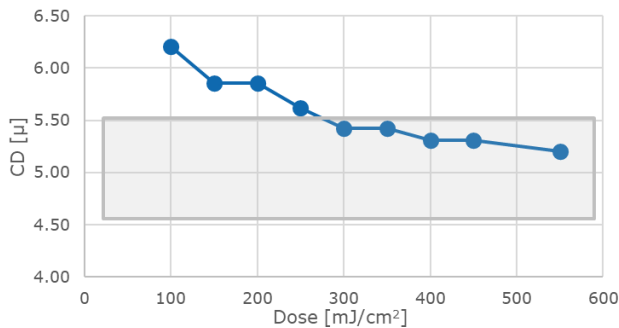


EXPOSURE LATITUDE FOR 5 μ M ISO. TRENCH@5 μ MFT

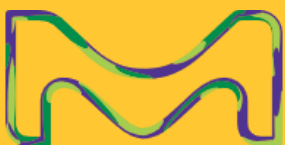
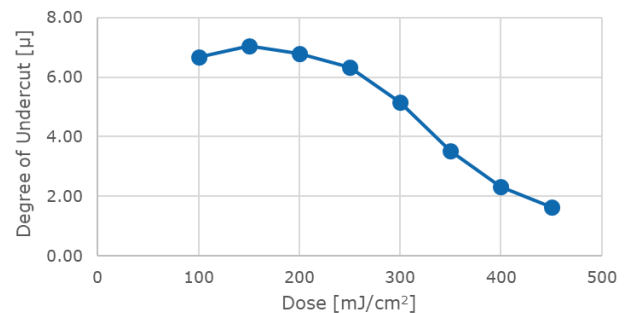


Focus: 1 μ m

Exposure Latitude

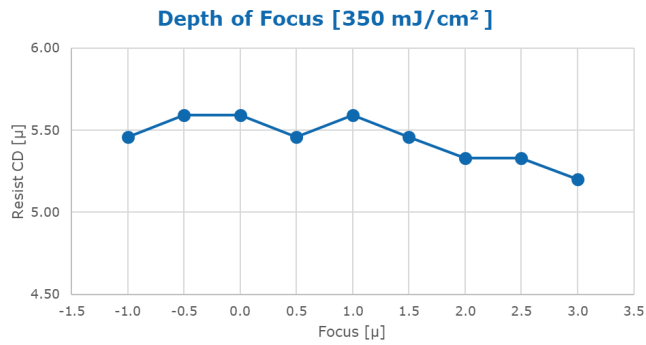
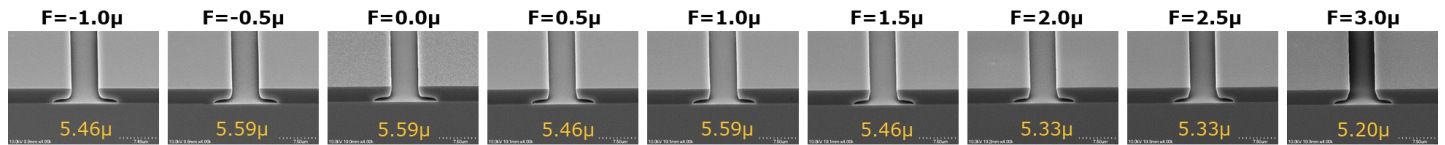


Degree of Undercut



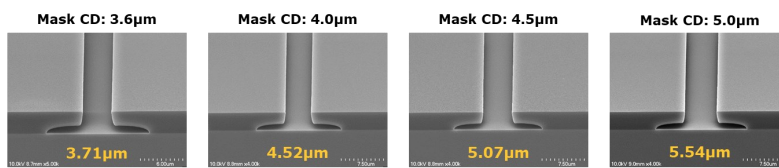
DEPTH OF FOCUS FOR 5UM ISO. TRENCH@5UMFT

[Energy: 350 mJ/cm²]

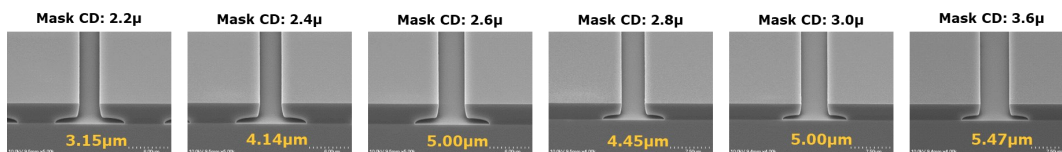


MASK LINEARITY FOR ISO. TRENCH@5UMFT

Linearity [300mJ/cm²]

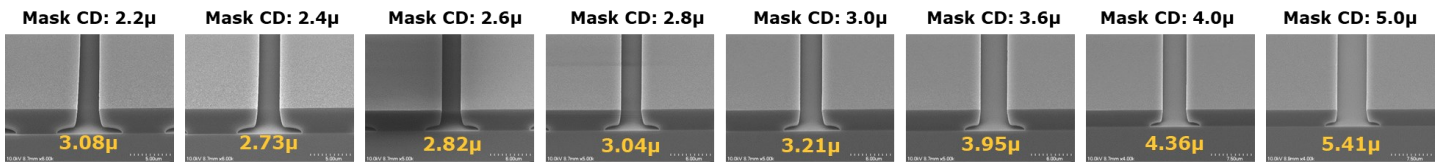


Linearity [350mJ/cm²]

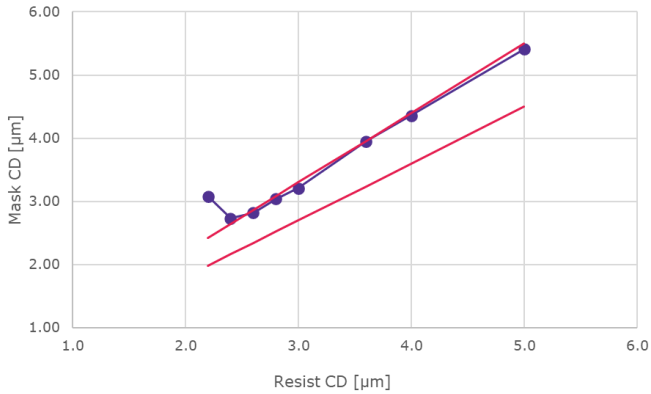


MASK LINEARITY FOR ISO. TRENCH@5UMFT

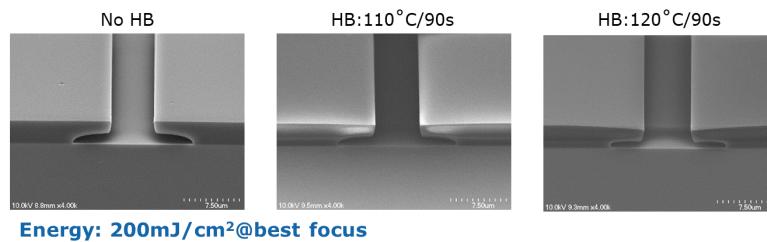
Linearity [400mJ/cm²]



Linearity



THERMAL STABILITY FOR 5UM ISO. TRENCH@5UMFT



AZ Exp LNR-003 exhibits stability upto 120°C

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